

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	14326	"tungsten silicide" or Wsi	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/13 15:33
2	BRS	L2	104859	polysilicon or poly-silicon or poly-si or polysi	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/13 15:33
3	BRS	L3	325002 8	phosphorus or phosphorous or phospho\$6 or P	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/13 15:33
4	BRS	L4	326340	"WF.sub.4" or "SiCl.sub.2H.sub.2" or "tungsten hexafluoride" or "dichlorosilane" or argon or Ar	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/13 15:33
5	BRS	L5	114	("tungsten silicide" or Wsi) same (polysilicon or poly-silicon or poly-si or polysi) same (phosphorus or phosphorous or phospho\$6 or P) same ("WF.sub.4" or "SiCl.sub.2H.sub.2" or "tungsten hexafluoride" or "dichlorosilane" or argon or Ar)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/13 15:33

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L6	8	((("tungsten silicide" or Wsi) same (polysilicon or poly-silicon or poly-si or polysi) same (phosphorus or phosphorous or phospho\$6 or P) same ("WF.sub.4" or "SiCl.sub.2H.sub.2" or "tungsten hexafluoride" or "dichlorosilane" or argon or Ar)) and (percent\$6)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/13 15:52
7	BRS	L7	9	((("tungsten silicide" or Wsi) same (polysilicon or poly-silicon or poly-si or polysi)) same (oxidiz\$6 near4 ((side adj wall) or sidewall or side-wall)) same (anneal\$6 or heat\$6 or thermal\$6)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/13 15:58

	Type	Hits	Search Text
1	BRS	14326	"tungsten silicide" or Wsi
2	BRS	104859	polysilicon or poly-silicon or poly-si or polysi
3	BRS	3250028	phosphorus or phosphorous or phospho\$6 or P
4	BRS	326340	"WF.sub.4" or "SiCl.sub.2H.sub.2" or "tungsten hexafluoride" or "dichlorosilane" or argon or Ar
5	IS&R	376	(438/584).CCLS.
6	BRS	4666	("tungsten silicide" or Wsi) near8 (polysilicon or poly-silicon or poly-si or polysi)
7	BRS	229	(oxidiz\$6 near4 ((side adj wall) or sidewall or side-wall)) near (short-time or (short near2 time) or second or sec! or min! or minute or anneal\$6 or heat\$6 or thermal\$6)
8	BRS	114	("tungsten silicide" or Wsi) same (polysilicon or poly-silicon or poly-si or polysi) same (phosphorus or phosphorous or phospho\$6 or P) same ("WF.sub.4" or "SiCl.sub.2H.sub.2" or "tungsten hexafluoride" or "dichlorosilane" or argon or Ar)
9	BRS	8	((("tungsten silicide" or Wsi) same (polysilicon or poly-silicon or poly-si or polysi) same (phosphorus or phosphorous or phospho\$6 or P) same ("WF.sub.4" or "SiCl.sub.2H.sub.2" or "tungsten hexafluoride" or "dichlorosilane" or argon or Ar)) and (percent\$6)
10	BRS	9	((("tungsten silicide" or Wsi) same (polysilicon or poly-silicon or poly-si or polysi)) same (oxidiz\$6 near4 ((side adj wall) or sidewall or side-wall)) same (anneal\$6 or heat\$6 or thermal\$6)
11	IS&R	2	("6346734").PN.
12	IS&R	2	("6251188").PN.

	DBs	Time Stamp
1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:00
2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:00
3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:01
4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:01
5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:01
6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:01
7	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:01
8	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:02
9	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:02
10	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:02
11	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:02
12	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:02

	Type	Hits	Search Text
13	IS&R	2	("6022586").PN.
14	BRS	18	((("tungsten silicide" or Wsi) near8 (polysilicon or poly-silicon or poly-si or polysi)) and ((oxidiz\$6 near4 ((side adj wall) or sidewall or side-wall)) near (short-time or (short near2 time) or second or sec! or min! or minute or anneal\$6 or heat\$6 or thermal\$6))

	DBs	Time Stamp
13	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:04
14	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/14 13:13

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	IS&R	L3	716	(438/595).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 15:18
2	BRS	L4	47	(("tungsten silicide" or Wsi) near8 (polysilicon or poly-silicon or poly-si or polysi)) and ((oxidiz\$6 near4 ((side adj wall) or sidewall or side-wall)) near8 (short-time or (short near2 time) or second or sec! or min! or minute or anneal\$6 or heat\$6 or thermal\$6))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 15:35
3	IS&R	L5	1093	(438/592).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 16:08
4	IS&R	L6	697	(438/652).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 16:39
5	IS&R	L7	634	(438/683).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 16:50

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	IS&R	L8	188	(438/684) .CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 17:06
7	IS&R	L9	433	(257/413) .CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 17:38
8	IS&R	L10	188	(257/407) .CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 17:50
9	IS&R	L11	678	(257/382) .CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 18:22
10	IS&R	L12	290	(257/383) .CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 18:35

	Type	L #	Hits	Search Text	DBs	Time Stamp
11	IS&R	L13	1032	(257/412).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 18:44
12	IS&R	L14	428	(257/900).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/07/14 18:59